

**UNITED STATES PATENT AND TRADEMARK OFFICE**

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**BEFORE THE PATENT TRIAL AND APPEAL BOARD**

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MICRON TECHNOLOGY, INC.,  
INTEL CORPORATION, AND  
GLOBALFOUNDRIES U.S., INC.,

Petitioners

v.

DANIEL L. FLAMM,

Patent Owner

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Case IPR No. Unassigned  
U.S. Patent No. 6,017,221  
Issued: January 25, 2000  
Named Inventor: Daniel L. Flamm

Title: PROCESS DEPENDING ON PLASMA DISCHARGES SUSTAINED BY  
INDUCTIVE COUPLING

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**DECLARATION OF DAVID B. GRAVES IN SUPPORT OF PETITION  
FOR *INTER PARTES* REVIEW OF U.S. PATENT NO. 6,017,221  
UNDER 35 U.S.C. §§ 311-319 AND 37 C.F.R. §§ 42.1-.80, 42.100-.123**

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